



**Corporate PR Contact**  
Molecular Imprints, Inc.  
Dave Gino  
1-512-339-7760

**Agency Contact**  
MCA  
David Moreno  
1-650-968-8900 ext. 125  
dmoreno@mcapr.com

## **INDUSTRY VETERANS JOIN MOLECULAR IMPRINTS' MANAGEMENT TEAM**

### **Paul Hofemann and Ben Eynon Each Assume Vice President Roles at Nanopatterning Leader**

AUSTIN, TX. July 1, 2008 – Molecular Imprints, Inc., the market and technology leader of nanopatterning systems and solutions, today announced that Ben Eynon and Paul Hofemann have joined its management team. These distinguished industry veterans are assuming the roles of vice president of marketing and business development for semiconductors, and vice president of marketing and business development for hard disk drives and emerging markets, respectively. Between them they possess nearly 40 years of combined experience in leadership positions at top semiconductor and data storage equipment and technology companies. The addition of these executives to Molecular Imprints is another indication of the company's growing momentum, as leading manufacturers and technologists alike increasingly recognize the unique advantages of its Step and Flash<sup>®</sup> Imprint Lithography (S-FIL<sup>®</sup>) technology.

Eynon and Hofemann will focus their efforts on accelerating Molecular Imprints' emergence as the world leader for sub-30nm patterning of non-volatile memory devices and storage systems by working closely with customers to provide the advanced solutions they require to succeed. Eynon will oversee development and integration efforts of Molecular Imprints' innovative S-FIL nanopatterning technology at leading semiconductor manufacturing companies, in addition to managing the company's development partnership with SEMATECH. Hofemann is responsible for expanding the company's leadership in the hard disk drive (HDD) industry. He will also drive the company's efforts in emerging nanopatterning growth opportunities in optical components, solid-state lighting, biotechnology and new environmentally friendly "green" applications.

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“Ben and Paul are both accomplished executives, who joined our team because they recognize the strength of our technology and the growing market opportunities ahead of us,” said Mark Melliar-Smith, CEO of Molecular Imprints. “Their arrival falls on the heels of two important milestones which also serve to highlight our growing momentum. Just over a month ago, we introduced the industry’s only high-speed, double-sided pilot-production-ready nanopatterning system for patterned media applications. On the semiconductor side of the business we recently announced a sale of our new Imprio 300 system to SEMATECH, a consortium of leading semiconductor manufacturers. Our customers will benefit from their technical and market experience and knowledge.”

Before joining Molecular Imprints, Eynon was the director of advanced lithography process development for Samsung and the associate director of lithography for SEMATECH. His industry experience also includes management positions at KLA-Tencor, Photronics, DuPont Photomasks and Texas Instruments. Hofemann previously held vice president-level roles in marketing and business development at Photronics, ADE and Veeco Instruments—where he worked on HDD and emerging applications. Hofemann also held management positions at KLA-Tencor, Semi-Gas Systems and Applied Materials.

**About Molecular Imprints, Inc.**

Molecular Imprints, Inc. (MII) is the technology leader for high-resolution, low cost-of-ownership nanopatterning systems and solutions in the hard disk drive (HDD) and semiconductor industries. MII is leveraging its innovative Step and Flash Imprint Lithography (S-FIL<sup>®</sup>) with Drop-on-Demand<sup>™</sup> material application technology to become the worldwide market and technology leader in high-volume patterning solutions for storage and memory devices, while enabling emerging markets in optics, biotechnology, and other industries. MII enables nanoscale patterning by delivering a comprehensive nanopatterning solution that is affordable, compatible and extendible to sub-10-nanometer resolution levels. For more information, visit [www.molecularimprints.com](http://www.molecularimprints.com).

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